

## Circuit Modeling of Ion Sensitive Field Effect Transistors with Current Drift

Dae Woong Kwon<sup>1</sup>, Sihyun Kim<sup>1</sup>, Ryoongbin Lee<sup>1</sup>, Dae Hwan Kim<sup>2</sup>, and Byung-Gook Park<sup>1</sup>

<sup>1</sup>Inter-University Semiconductor Research Center (ISRC) and Department of Electrical Engineering and Computer Science (EECS), Seoul National University, Seoul 151-742, Korea

<sup>2</sup>School of Electrical Engineering, Kookmin University, Seoul 136-702, Korea  
dw79kwon@snu.ac.kr

### Summary

In terms of the application of ion sensitive field effect transistors (ISFETs) to integrated circuits, the macro model of ISFETs is required. Although several models have been reported [1,2], there is no electrical model that reflects the time-dependent drain current ( $I_D$ ) change (drift effect). We propose the electrical model which can reflect the drift effect and can be expressed by the combination of electrical circuit components. In the proposed model,  $R_1$  represents the resistance of the electrolyte and the FET can be approximated by the capacitances  $C_1$  (capacitance of pure gate oxide in which hydrogen ions move very slowly) and  $C_2$  (capacitance by gate oxide with defects in which hydrogen ions move relatively faster). Furthermore, the movement of hydrogen ions in the defective oxide is represented by  $R_2$  and the current drift is modeled as the parallel combination of the  $C_2$  and the  $R_2$  because the drift effect is strongly related to hydrogen ion movement through defective gate oxide or Helmholtz layer. Consequently, the ISFET with current drift can be modeled by the series connection of the  $R_1$ , the parallel combination of the  $C_2$  and the  $R_2$ , and the  $C_1$ . Also, the measured time-dependent current of the ISFET is successfully fitted to the proposed model.

### Results and Discussion

To verify the validity of the proposed compact model, fabricated silicon nanowire (SiNW) ISFETs are measured transiently at fixed liquid gate bias ( $V_{LG}$ ) and drain bias ( $V_D$ ) of 1 V. Figs. 1 (a) and (b) show the schematics of the SiNW ISFET and the measurement system for pH sensing, respectively. The details of the fabrication and the measurement procedure were demonstrated in the previous report [3].

Firstly, we presume that the long time constant of the  $I_D$  drift is related to the effect of hydrogen ion movement through oxide or Helmholtz layer (HL). To model this effect, we set up a simple circuit as shown in Fig. 2(a) where  $R_1$  represents the resistance of the electrolyte and the FET can be approximated as capacitances,  $C_1$  and  $C_2$ .  $C_2$  is the capacitance by gate oxide with defects in which the hydrogen ions move relatively faster than that of pure oxide.  $C_1$  is the capacitance of the pure oxide in which the hydrogen ions move very slowly.  $R_2$  represents the ion movement through the defective oxide. The low diffusion constant in the oxide causes the bottleneck of the ion motion. The slow movement of hydrogen ions in the defective oxide is modeled as the parallel combination of the  $C_2$  and the large resistance  $R_2$ . The parameters for the circuit model are summarized in Table 1(a).

The input loop needs to be considered for the analysis of the response to the  $V_{LG}$  (a unit step function). According to Kirchhoff's law, the  $V_{LG}$  is expressed by the circuit components,  $C_1$ ,  $C_2$ ,  $R_1$ ,  $R_2$  and the voltage across HL ( $V_G$ ). By using Laplace transform for  $V_{LG} = V_G$  with some approximation that drift term ( $C_2$ ,  $R_2$ ) are much larger than rapid changing term ( $C_1$ ,  $R_1$ ), we obtain the relation between  $V_{LG}$  and  $V_G$  as shown in the equation of Fig. 2(a). The physical meaning and notation of the parameters in the equation are summarized in Table 1(b). However, the voltage drift cannot be measured directly in the experiment. Thus, the  $I_D$  is calculated by the equation of Fig. 2(b) including the proposed model and the calculated  $I_D$  is compared with measured data as shown in Fig. 2(b). It is verified that the model consisting of only electrical circuit components reflects successfully the drift effect related to hydrogen ion reaction.

### Acknowledgment

This work was supported by the Brain Korea 21 Plus Project in 2016 and National Research Foundation of Korea through the Ministry of Science, ICT and Future Planning (Grant No. 2013R1A1A2065339).

Please note "POSTER" here, if you want to submit a poster presentation (format "IMCS\_Indicator").

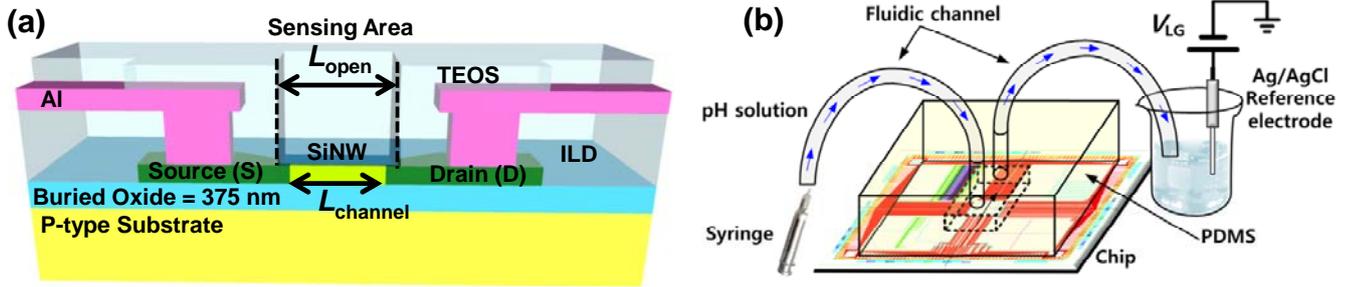


Fig. 1: (a) Schematic diagram of fabricated SiNW ISFET. (b) Measurement system for pH sensing

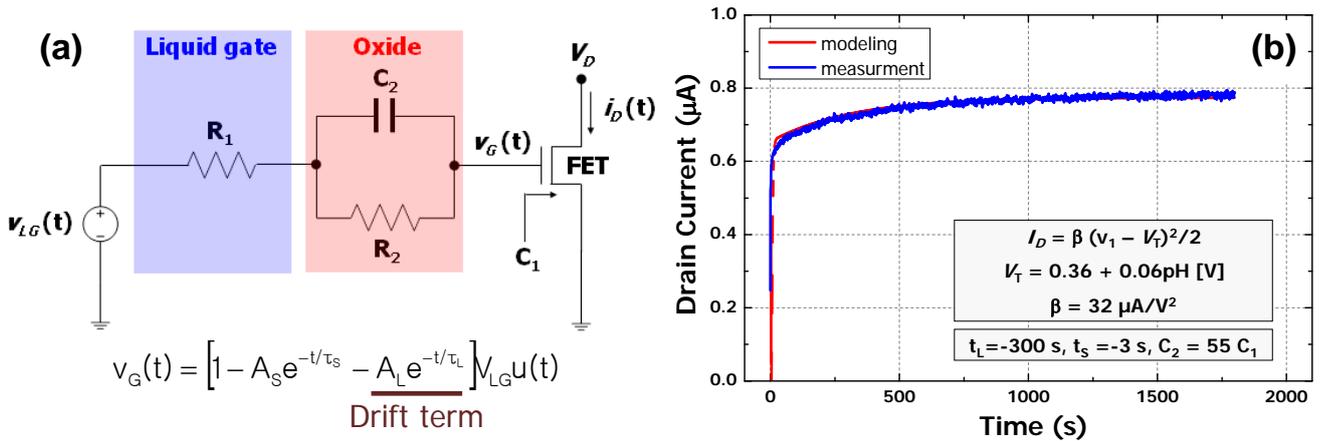


Fig. 2: (a) A schematic model including drift effect. It is composed of electrical components. (b) Comparison of measured and calculated currents by using proposed model.

(a)			(b)		
Notation	Component	Reaction rate	Notation	Components	Physical meaning
$C_1$	Gate capacitance without $H^+$ movement	Fast response	$\tau_L$	$(C_1 + C_2)R_2$	long time constant
$R_1$	Resistance of electrolyte		$\tau_S$	$C_1 C_2 R_1 / (C_1 + C_2)$	short time constant
$C_2$	Gate capacitance with $H^+$ movement	Slow response	$A_L$	$\frac{C_2}{C_1 + C_2}$	initial state for $\tau_L$
$R_2$	Resistance of $H^+$ at oxide		$A_S$	$\frac{C_1}{C_1 + C_2}$	initial state for $\tau_S$

Table. 1: (a) Parameters for electrical circuit model. (b) Notations for simple expression and its components and physical meaning.

## References

- [1] Sergio Martinoia, and Giuseppe Massobrio, Sens. Actuators B 62, 182 (2000).
- [2] W.-W. Chung, F.-S. He, C.-H. Yang, and M.-C. Wang, Journal of Med. and Biolog. Engineering 26, 29 (2005).
- [3] J. Lee, J.-M Lee, J. H. Lee, W. H. Lee, M. Uhm, B.-G. Park, D. M. Kim, Y.-J. Jeong, and D. H. Kim, IEEE Electron Device Letters 33, 1768 (2012).